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(12) **United States Design Patent**
Sugiura et al.

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(54) **RETAINER PLATE OF TOP HEATER FOR WAFER PROCESSING FURNACE**

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(73) Assignee: **KOKUSAI ELECTRIC CORPORATION**, Tokyo (JP)

(**) Term: **15 Years**

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(30) **Foreign Application Priority Data**

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(51) **LOC (13) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**; D15/144.1

(58) **Field of Classification Search**
USPC D13/182, 184, 199, 123; D15/144, D15/144.1, 144.2, 140, 199; 156/345.12, 156/345.13, 345.14, 471, 472, 345.37, 156/345.62, 912; 451/173, 177, 28, 282, 451/286, 287, 288, 290, 296, 307, 398, 451/51; 118/728
CPC H01L 21/67098; H01L 21/67103; H01L 21/67109; H01L 21/67115; H01L 21/67; H01L 21/673; H01L 21/6735; H01L 21/67369; H01L 21/67011; H01L 21/67757; B24B 5/00; B24B 37/27; B24B 37/30; B24B 37/32; B24B 29/00; B24B 7/22; B24B 7/228; C23C 16/4587; C23C 16/45546; C23C 16/4584; C23C 16/46; C23C 16/458
See application file for complete search history.

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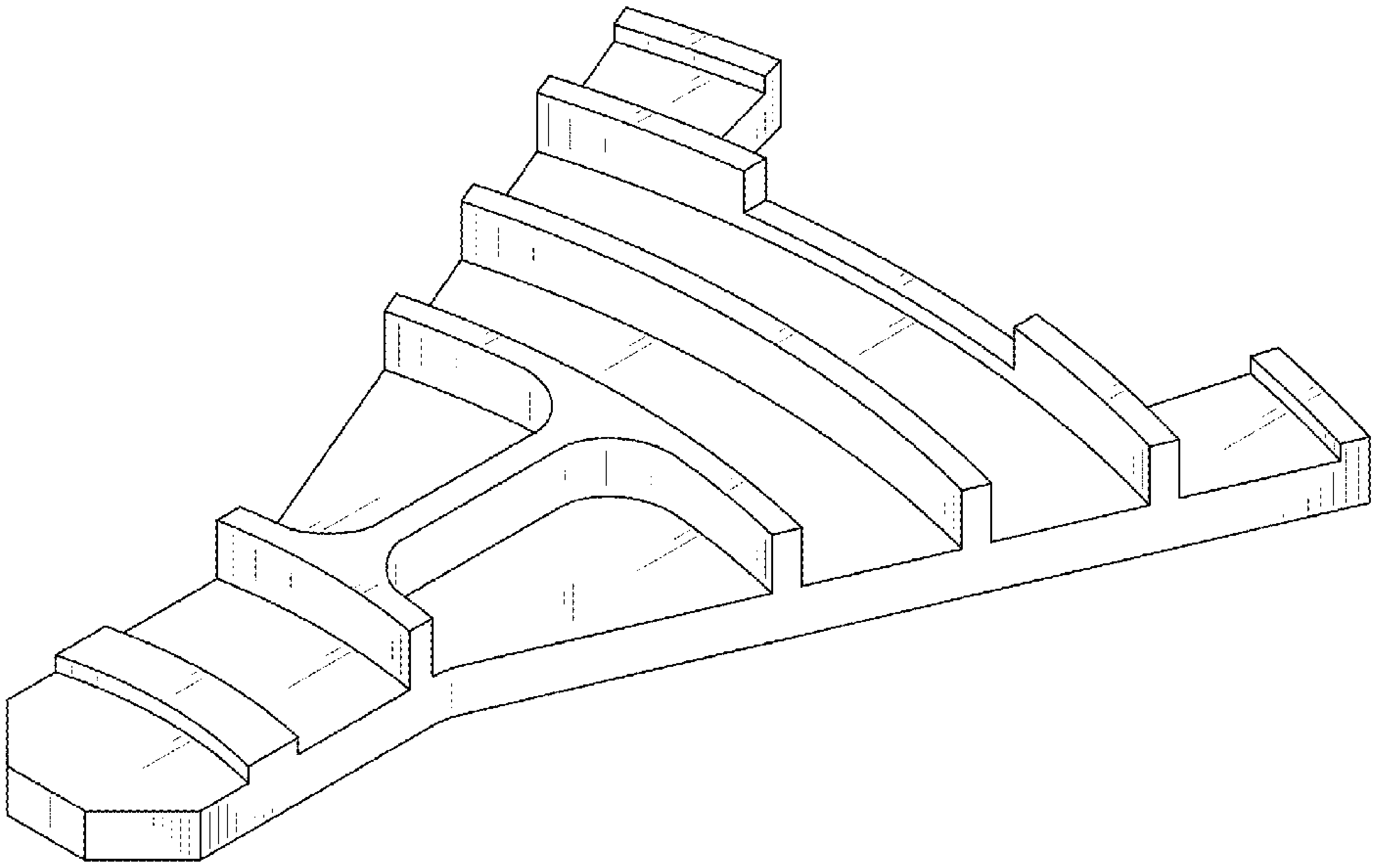
(57) **CLAIM**

The ornamental design for a retainer plate of top heater for wafer processing furnace, as shown and described.

DESCRIPTION

FIG. **1** is a front, top and right side perspective view of a retainer plate of top heater for wafer processing furnace showing our new design;
FIG. **2** is a front elevational view thereof;
FIG. **3** is a left side elevational view thereof;
FIG. **4** is a right side elevational view thereof;
FIG. **5** is a top plan view thereof; and
FIG. **6** is a bottom plan view thereof.
FIG. **7** is a rear elevational view thereof; and,
FIG. **8** is a cross-sectional view taken along line **8-8** in FIG. **2**.

1 Claim, 6 Drawing Sheets



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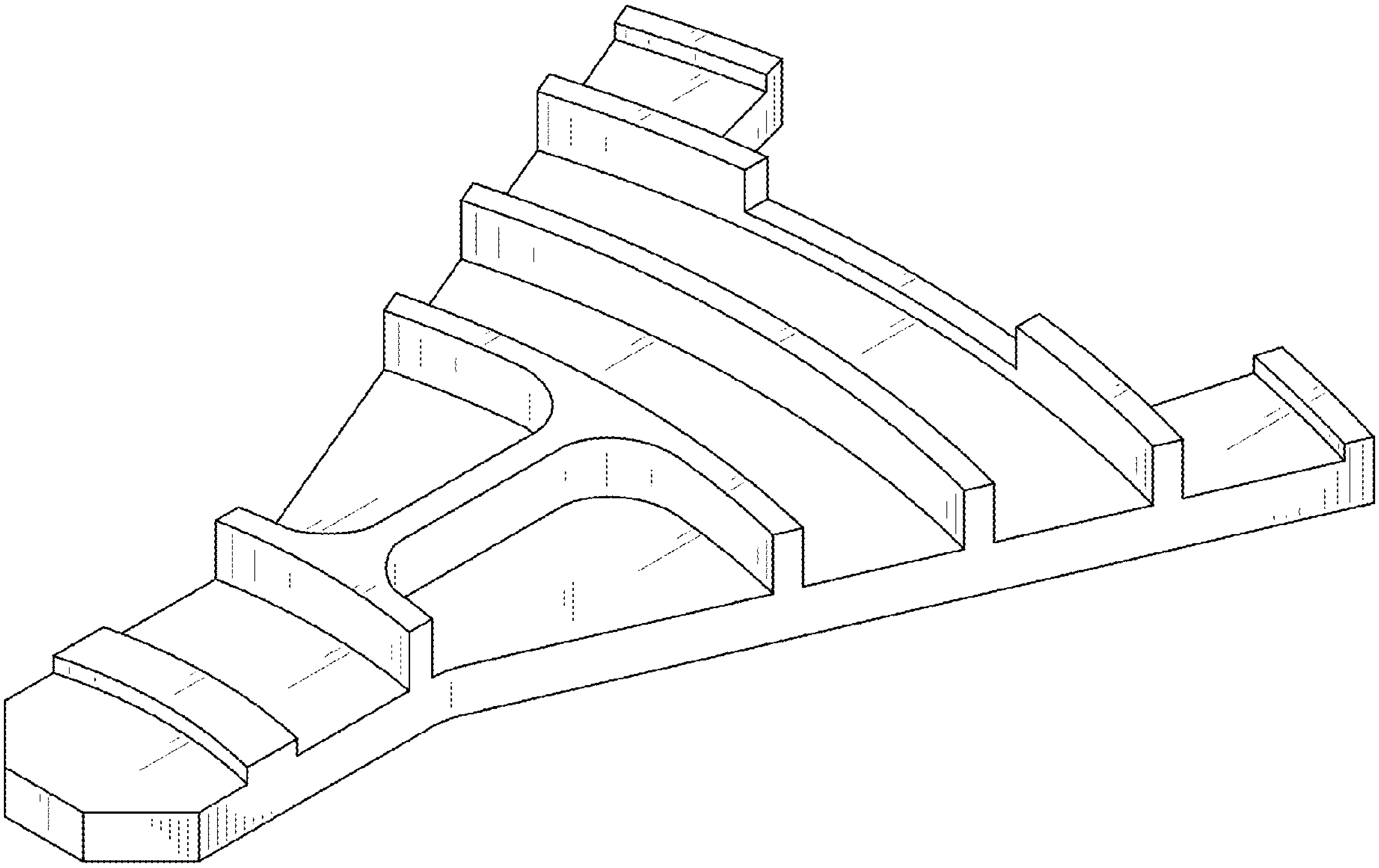

FIG. 1

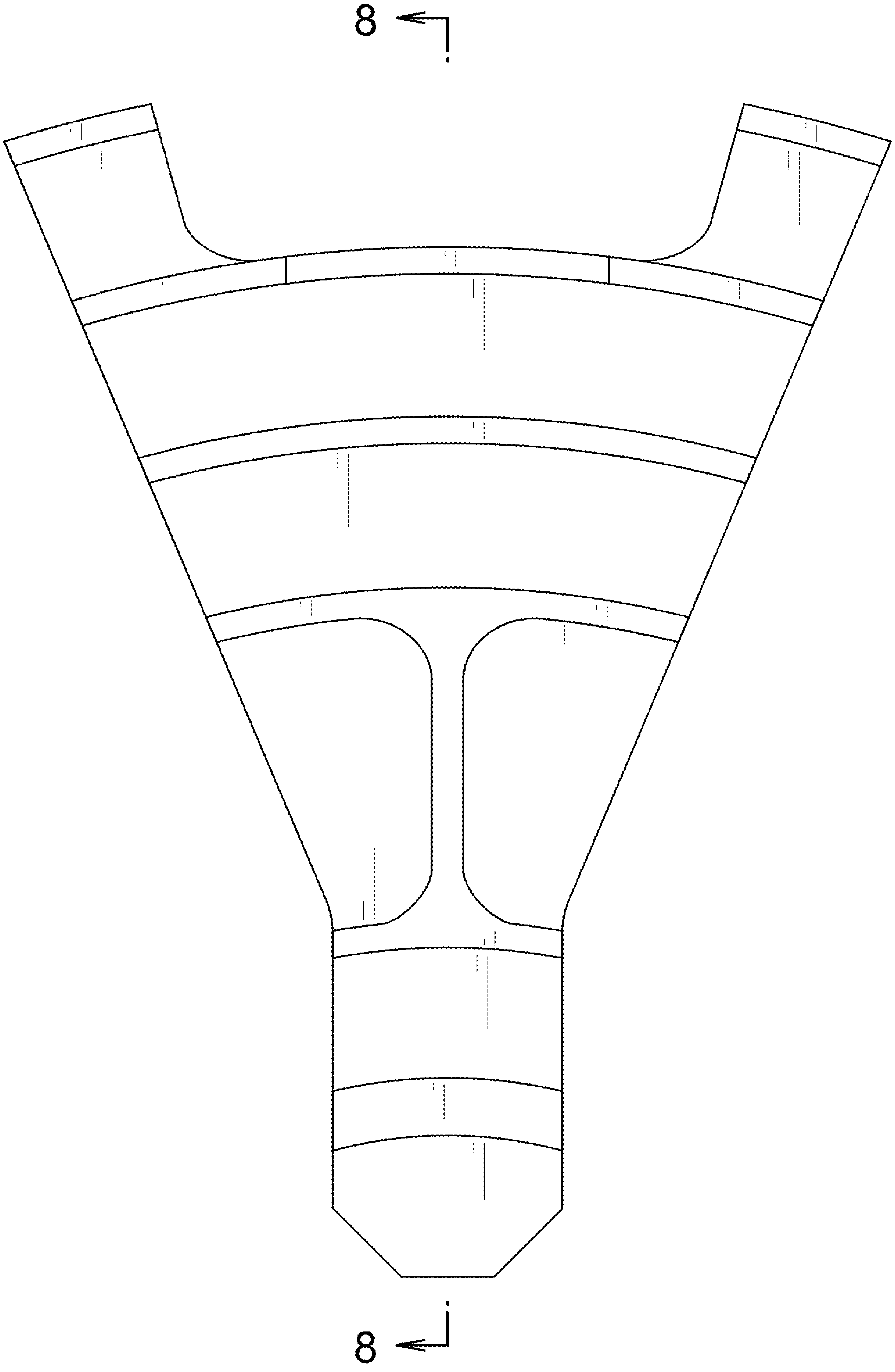

FIG. 2

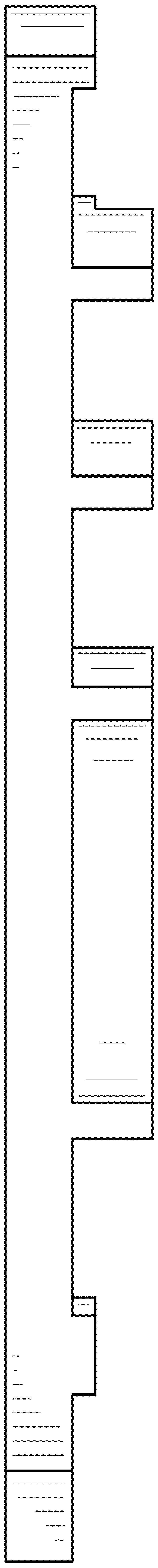

FIG. 3

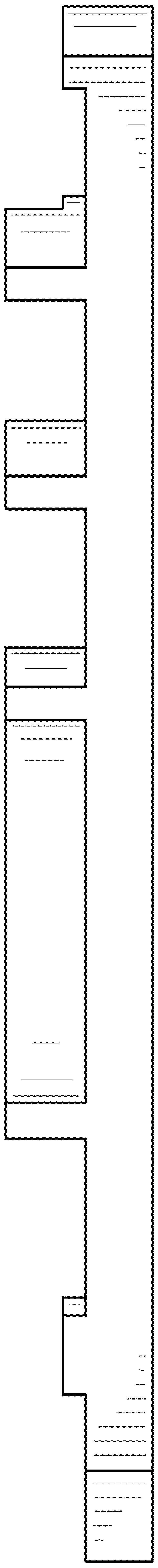

FIG. 4

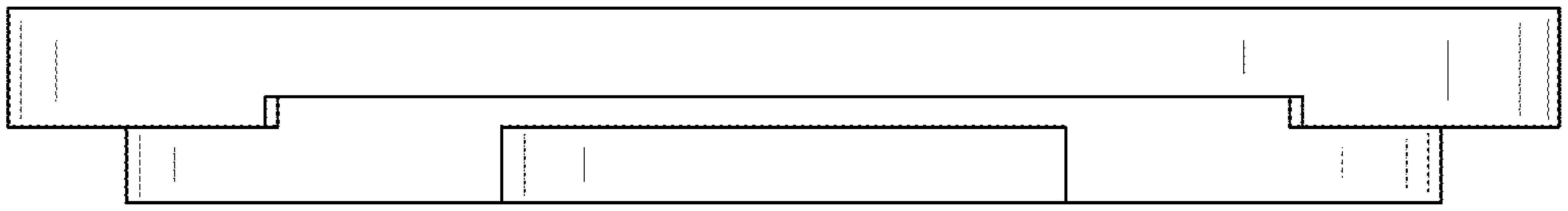

FIG. 5

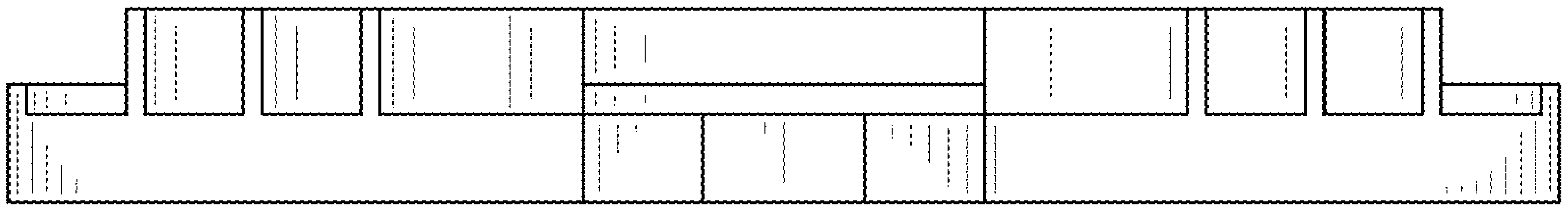

FIG. 6

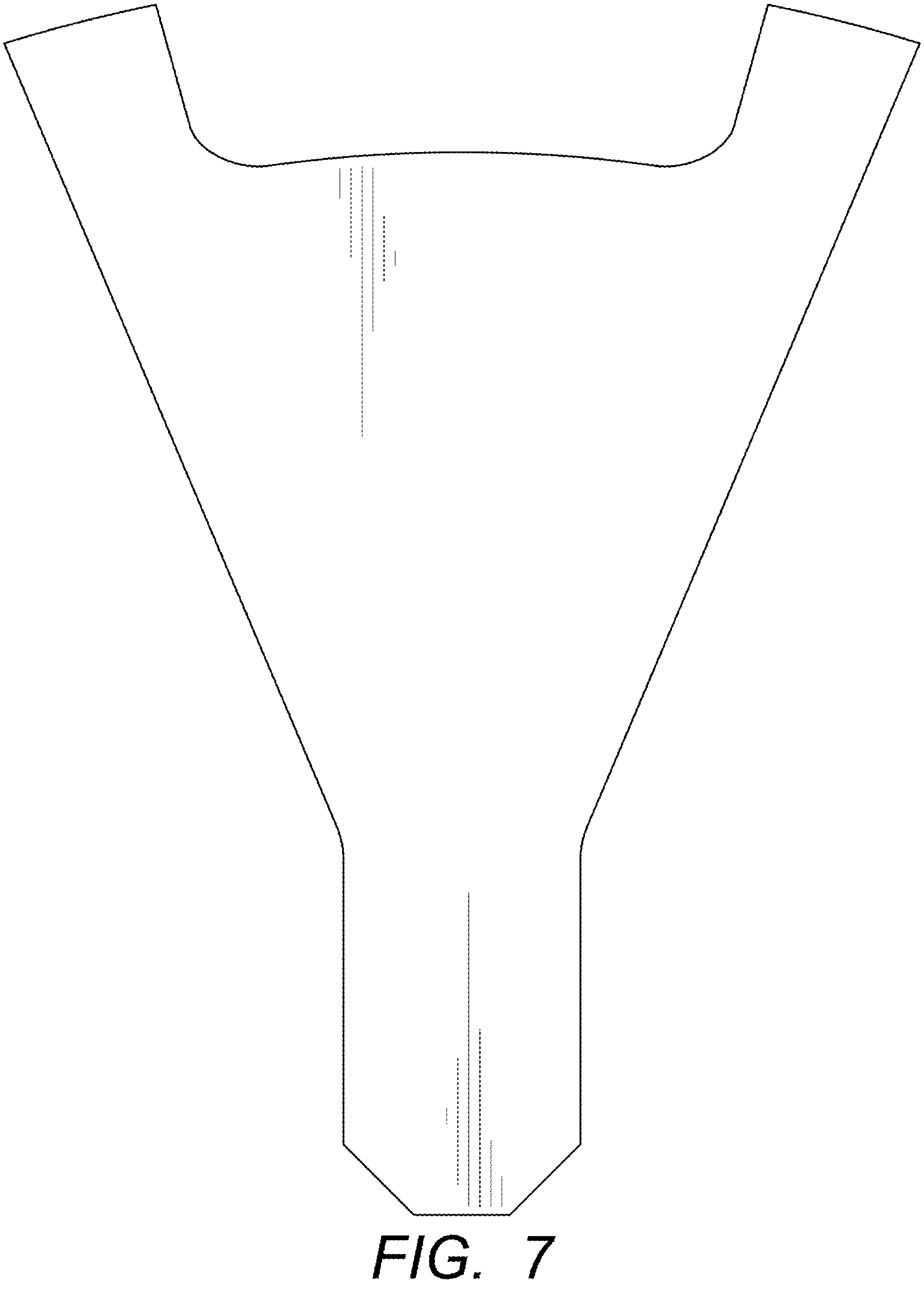

FIG. 7

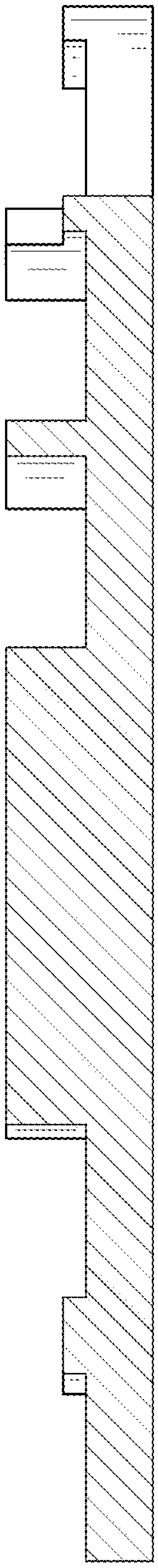

FIG. 8